

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Original) An exposure apparatus which exposes a substrate by radiating an exposure light beam onto the substrate through a liquid, the exposure apparatus comprising:  
a projection optical system which projects an image of a pattern onto the substrate; and  
a substrate table which holds the substrate, wherein:  
a member, at least a part of a surface of which is liquid-repellent, is provided exchangeably on the substrate table.
2. (Original) The exposure apparatus according to claim 1, wherein the member is exchanged depending on deterioration of liquid repellence thereof.
3. (Original) The exposure apparatus according to claim 1, wherein the member has a flat portion which is substantially flush with a surface of the substrate held by the substrate table.
4. (Original) The exposure apparatus according to claim 3, wherein the flat portion is arranged around the substrate.
5. (Original) The exposure apparatus according to claim 4, further comprising an attaching/detaching mechanism which attaches/detaches the member with respect to the substrate table.
6. (Original) The exposure apparatus according to claim 5, wherein the attaching/detaching mechanism is capable of detaching the member from the substrate table together with the substrate.
7. (Original) The exposure apparatus according to claim 1, wherein at least the liquid-repellent part of the member is formed of polytetrafluoroethylene.

8-11. (Canceled)

12. (Original) An exposure apparatus which exposes a substrate by radiating an exposure light beam onto the substrate through a liquid, the exposure apparatus comprising:

a projection optical system which projects an image of a pattern onto the substrate; and

a movable stage which is movable relative to the projection optical system, wherein:

a liquid-repellent member, at least a part of which is liquid-repellent, is provided on the movable stage, and the liquid-repellent member is exchangeable.

13. (Original) The exposure apparatus according to claim 12, wherein the movable stage has at least one of a measuring stage and a substrate stage which holds the substrate.

14. (Original) The exposure apparatus according to claim 12, wherein the movable stage has a plurality of stages.

15. (Original) The exposure apparatus according to claim 12, wherein the liquid-repellent member is exchanged depending on deterioration of liquid repellence thereof.

16. (Original) The exposure apparatus according to claim 12, wherein the movable stage is a substrate stage which holds the substrate, and the substrate stage includes a holding portion which holds the member, and an attracting unit which detachably attaches the member to the holding section.

17. (Original) The exposure apparatus according to claim 16, wherein the liquid-repellent member is a stepped member having a first surface which is opposed to a back surface of the substrate and a second surface which extends to outside of the substrate along a surface of the substrate.

18. (Original) The exposure apparatus according to claim 17, wherein at least the second surface is liquid-repellent.

19. (Original) The exposure apparatus according to claim 17, further comprising an outer member which has a third surface extending to outside of the liquid-repellent member along the surface of the substrate and which is engageable with the liquid-repellent member, wherein at least the third surface is liquid-repellent.

20. (Original) The exposure apparatus according to claim 17, further comprising a lifting unit which moves the liquid-repellent member upwardly and downwardly with respect to the holding section.

21. (Original) The exposure apparatus according to claim 20, wherein the lifting unit moves the liquid-repellent member upwardly from the holding section in a state in which the liquid-repellent member supports the substrate.

22. (Original) The exposure apparatus according to claim 16, wherein the liquid-repellent member is a substrate holder having a support portion which supports an edge portion of a back surface of the substrate, a flat surface which extends to outside of the substrate along a surface of the substrate, and a side wall which is connected to the flat surface and which is higher than the flat surface.

23. (Original) The exposure apparatus according to claim 22, further comprising a substrate table on which a substrate holder is placed, wherein the substrate holder and the substrate table have flow passages to make communication with each other respectively.

24. (Original) The exposure apparatus according to claim 12, wherein the part of the member, which is liquid-repellent, is composed of fluoride.

25. (Original) The exposure apparatus according to claim 12, wherein the liquid-repellent member includes at least a part of a reference member and a part an optical sensor.

26. (Original) The exposure apparatus according to claim 25, wherein at least a part of a light irradiated surface of each of the reference member and the optical sensor is liquid-repellent.

27. (Original) The exposure apparatus according to claim 12, wherein the part of the liquid-repellent member, which is liquid-repellent, has a light irradiated surface; an adhesive layer is formed on the light irradiated surface; and an amorphous fluororesin layer is formed on a surface of the adhesive layer.

28. (Original) The exposure apparatus according to claim 27, wherein the adhesive layer is formed of at least one particulate layer selected from the group consisting of silicon dioxide, magnesium fluoride, and calcium fluoride.

29. (Original) The exposure apparatus according to claim 27, wherein the adhesive layer is a layer which is obtained by etching the light irradiated surface with hydrogen fluoride.

30. (Original) The exposure apparatus according to claim 12, wherein the substrate is a circular substrate having no cutout, and a surface and a side portion of the substrate are coated with a photosensitive material.

31. (Original) The exposure apparatus according to claim 12, wherein an exchange timing for the member is determined on the basis of decrease in contact angle of the liquid at the liquid-repellent part of the member.

32. (Original) The exposure apparatus according to claim 31, wherein the member is exchanged when the contact angle is decreased to be not more than  $100^{\circ}$ .

33. (Original) The exposure apparatus according to claim 31, wherein the member is exchanged when the contact angle is decreased by not less than  $10^{\circ}$  as compared with an initial state.

34. (Original) The exposure apparatus according to claim 12, wherein the movable stage includes a substrate stage which holds the substrate, and the member forms a flat surface around the substrate held by the substrate stage.

35. (Original) The exposure apparatus according to claim 34, wherein a surface of the substrate held by the substrate stage is substantially flush with the flat surface disposed therearound.

36. (Original) The exposure apparatus according to claim 12, wherein the movable stage has an attracting unit which attracts and holds the member.

37. (Original) The exposure apparatus according to claim 12, wherein the liquid-repellent part of the member is formed of a material which is deteriorated by being irradiated with ultraviolet light.

38. (Original) An exposure method for performing liquid immersion exposure for a substrate by radiating an exposure light beam onto the substrate through a liquid, the exposure method comprising:

supplying the liquid to at least a part of a surface of the substrate; and

performing the liquid immersion exposure for the substrate by radiating the exposure light beam onto the substrate through the liquid, wherein:

a part of the exposure apparatus, which is different from the substrate for which the liquid is supplied, is liquid-repellent, and the liquid-repellent part of the exposure apparatus is exchanged depending on deterioration of liquid repellence thereof.

39. (Original) The exposure method according to claim 38, wherein the part of the exposure apparatus is a part of a substrate stage or a part of a measuring stage.

40. (Original) The exposure method according to claim 39, wherein the part of the substrate stage is exchanged together with the substrate.

41. (Original) The exposure method according to claim 38, wherein the deterioration of the liquid repellence is judged depending on a totalized amount of radiation of ultraviolet light.

42-59. (Canceled)

60. (New) The exposure apparatus according to claim 1, wherein the member includes a reference member having an irradiated surface, at least a part of which is liquid-repellent.

61. (New) The exposure apparatus according to claim 60, wherein the member is exchanged depending on deterioration of liquid repellence thereof.

62. (New) The exposure apparatus according to claim 60, wherein the member has a flat portion which is substantially flush with a surface of the substrate held by the substrate table.

63. (New) The exposure apparatus according to claim 60, wherein the liquid-repellent member further includes at least a part of an optical sensor.

64. (New) The exposure apparatus according to claim 63, wherein at least a part of a light irradiated surface of the optical sensor is liquid-repellent.

65. (New) The exposure apparatus according to claim 63, wherein the optical sensor is an illuminance sensor.

66. (New) The exposure apparatus according to claim 65, wherein the illuminance sensor measures a radiation amount of the exposure light beam.

67. (New) The exposure apparatus according to claim 63, wherein the optical sensor is a spatial image-measuring sensor.

68. (New) The exposure apparatus according to claim 63, wherein the optical sensor is a wavefront aberration-measuring sensor.

69. (New) The exposure apparatus according to claim 60, wherein the substrate table is movable with respect to the projection optical system.

70. (New) The exposure apparatus according to claim 60, wherein at least the liquid-repellent part of the reference member is formed of polytetrafluoroethylene.

71. (New) The exposure apparatus according to claim 60, wherein the member includes a surface member having a flat portion which is substantially flush with a surface of the substrate held by the substrate table, and the surface member is detachable independently from the reference member.

72. (New) The exposure apparatus according to claim 1, wherein the member includes a part of an optical sensor having an irradiated surface, at least a part of which is liquid-repellent.

73. (New) The exposure apparatus according to claim 72, wherein at least a part of a light irradiated surface of the optical sensor is liquid-repellent.

74. (New) The exposure apparatus according to claim 72, wherein the optical sensor is an illuminance sensor.

75. (New) The exposure apparatus according to claim 74, wherein the illuminance sensor measures a radiation amount of the exposure light beam.

76. (New) The exposure apparatus according to claim 72, wherein the optical sensor is a spatial image-measuring sensor.

77. (New) The exposure apparatus according to claim 72, wherein the optical sensor is a wavefront aberration-measuring sensor.

78. (New) The exposure apparatus according to claim 72, wherein the substrate table is movable with respect to the projection optical system.

79. (New) The exposure apparatus according to claim 72, wherein at least the liquid-repellent part of the reference member is formed of polytetrafluoroethylene.

80. (New) The exposure apparatus according to claim 72, wherein the member includes a surface member having a flat portion which is substantially flush with a surface of the substrate held by the substrate table, and the surface member is detachable independently from the reference member.

81. (New) The exposure apparatus according to claim 12, wherein the liquid-repellent member includes a reference member having an irradiated surface, at least a part of which is liquid-repellent.

82. (New) The exposure apparatus according to claim 81, wherein the movable stage has at least one of a measuring stage and a substrate stage which holds the substrate.

83. (New) The exposure apparatus according to claim 81, wherein at least the liquid-repellent part of the reference member is formed of polytetrafluoroethylene.

84. (New) The exposure apparatus according to claim 81, wherein the liquid-repellent member includes a surface member having a flat portion which is substantially flush with a surface of the reference member, and the surface member is detachable independently from the reference member.

85. (New) The exposure apparatus according to claim 12, wherein the member includes a part of an optical sensor having an irradiated surface, at least a part of which is liquid-repellent.

86. (New) The exposure apparatus according to claim 85, wherein at least a part of a light irradiated surface of the optical sensor is liquid-repellent.

87. (New) The exposure apparatus according to claim 85, wherein the optical sensor is an illuminance sensor.

88. (New) The exposure apparatus according to claim 87, wherein the illuminance sensor measures a radiation amount of the exposure light beam.



89. (New) The exposure apparatus according to claim 85, wherein the optical sensor is a spatial image-measuring sensor.

90. (New) The exposure apparatus according to claim 85, wherein the optical sensor is a wavefront aberration-measuring sensor.

91. (New) The exposure apparatus according to claim 85, wherein the substrate table is movable with respect to the projection optical system.

92. (New) The exposure apparatus according to claim 85, wherein at least the liquid-repellent part of the reference member is formed of polytetrafluoroethylene.

93. (New) The exposure apparatus according to claim 85, wherein the member includes a surface member having a flat portion which is substantially flush with a surface of the substrate held by the substrate table, and the surface member is detachable independently from the reference member.

94. (New) The exposure method according to claim 38, wherein an exchange timing for the liquid-repellent part is determined on the basis of a decrease in a contact angle of the liquid at the liquid repellent part.

95. (New) The exposure method according to claim 94, wherein the member is exchanged when the contact angle is decreased to be not more than 100 degrees.

96. (New) The exposure method according to claim 95, wherein the member is exchanged when the contact angle is decreased by not less than 10 degrees as compared with an initial state.

97. (New) An exposure method for performing liquid immersion exposure for a substrate by radiating an exposure light beam onto the substrate via a projection optical system and a liquid, the exposure method comprising:

providing a member, at least a part of a surface of which is liquid-repellent, on a substrate table, the substrate table holding the substrate,

performing the liquid immersion exposure for the substrate held by the substrate table; and

exchanging the member after performing the liquid immersion exposure for the substrate.

98. (New) A method for producing a device comprising:

exposing a substrate by the exposure method as defined in claim 97; and

assembling a device from the exposed substrate.